Odisha Computer Application Centre (OCAC)
Plot No. N-1/7-D, Acharya Vihar, Bhubaneswar – 751013

Our Ref. No. OCAC-IFITP-IP-0007-2025 3094 **/ Date** 17/06/2025

Short Quotation Call Notice for Appointment of Registered Valuer

OCAC invites quotations from Registered Valuers (under Companies Act, 2013) for undertaking valuation of capital equipment procured by a company establishing a Compound Semiconductor manufacturing facility in Odisha and a beneficiary under the Odisha Semiconductor Manufacturing and Fabless Policy.

The scope of work includes:

- Inspection and assessment of the equipment listed at Annexure:
- Procurement Year: 2021-22
- Procurement Cost: INR 20.00 Cr (Approx.)
- Location: Flatted Factory Building, Infovalley, Bhubaneswar, Dist-Khurda, Odisha
- Estimation of Fair Market Value
- Assessment of Remaining Useful Life
- Submission of a comprehensive Valuation Report

Interested Registered Valuers may submit:

1. A technical and financial proposal including their credentials and experience
2. Quoted professional fee (excluding travel and lodging)
3. Copy of valid registration certificate
4. GST Registration Certificate

Other important T&C:

1. The valuer must have at least 5 years of experience and must have undertaken at least two assignments with valuation of P&M not less than INR 15 Cr each in the last 3 years. One of the two assignments should be preferably from a government organization.
2. All relevant information and details sought by the valuer as part of the valuation process will be facilitated by OCAC.

3. Return airfare and local hospitality will be reimbursed for the Valuer (Only for the valuer from outside the Bhubaneswar). Manpower support for onsite inspection etc. will be provided locally (borne by RIR Power Electronics Ltd.).
4. The assignment is time-bound and should be completed within 7 working days of award of contract.
5. Submission Deadline: Seven working days from issue (on or before 5:30 P.M. of dated 25.06.2025)
6. Mode: Physical Mode (All tender documents shall be submitted in a sealed envelope or securely packaged)
7. OCAC reserves the right to accept or reject any or all offers without assigning any reason thereof.

Note:

- Location of above assets: Flatted Factory Building, EMC Park, Infovalley, District Khordha, Odisha
- Further details of the equipment to be shared at the time of visit

17.6.2025

Administrative Officer

Copy to:

1. PA to M.D., OCAC for kind information of M.D., OCAC.
2. G.M. (Admin), OCAC for kind information
3. CGM (Finance), OCAC for kind information.
4. Notice Board for information of all bidders.
5. Sri B. K. Mohanty, DPO to publish the notice in OCAC website.

Annexure

Sr. No.	Plant and Machinery	Brief Description and use	Date of Original Invoice
1	Silicon Carbide Epitaxy Reactor 1 PE106	SiC chemical vapor deposition (CVD) Reactor. It is a combination of Reactor unit, Power Generator, Process Pump, Bubbler and other relevents parts used for Epitaxy process	12-Apr-21
2	Central Hollow Purifier for Hydrogen Gas	It is a gas purifier that uses Hollow Fiber Membrane technology to purify large flow of Hydrogen gas for EPI reactor.	14-Apr-22
3	Central Heated Purifier for Nitrogen Gas	This purifier removes impurity from nitrogen gas and performs impurities adsorption at an operating temperature of 350℃~400℃.	14-Apr-22
4	Central Hollow Purifier for Agron Gas	It is a gas purifier that uses Hollow Fiber Membrane technology to purify large flow of Argon gas for EPI reactor.	14-Apr-22
5	Ambient Temprerature Catalyst Purifier Argon Gas (POU)	This purifier is used to purify in line Argon gas. It uses catalyst based technology to absorb oxygen (O2), water (H2O), carbon monoxide (CO), carbon dioxide (CO2), and hydrogen (H2) impurities in bulk gases.	14-Apr-22
6	Ambient Temperature Catalyst Purifier Hydrogen Gas (POU)	This purifier is used to remove oxygen (O2), water (H2O), carbon monoxide (CO) and carbon dioxide (CO2) from Hydrogen.	14-Apr-22
7	Ambient Temperature Catalyst Purifier Nitrogen Gas (POU)	This purifier is used to remove oxygen (O2), water (H2O), carbon monoxide (CO), carbon dioxide (CO2), and hydrogen (H2) from Nitrogen	14-Apr-22

		and inert gases.	
8	Gas purifier Ethelene C2H4	Entegris Point of use Ethelene gas purifier system. It is used in purification of Ethelene at the instrument end.	12-Oct-21
9	Wet Scrubber System	Wet scrubber for single chamber epitaxy reactor. The scrubber is useful for neutralization of harmful gases produced during the epitaxial deposition process.	12-May-21
10	Miscellaneous items for CVD installation	Multiple parts related to gas distributions and installation.	6-Sept-22 & 16-Nov-22
11	Water Chiller	Water Chiller to cool down the process water	18-Sept 21 & 2-Mar-22
12	Laptop	Laptop with high end processor	21-Jan-21